L	Hits	Search Text	DB	Time stamp
Number				
1	1	("6218248").PN.	USPAT;	2004/01/27
_	_		US-PGPUB	13:11
2	3	(("5929488") or ("5889293") or	USPAT;	2004/01/27
_	_	("20010025991")).PN.	US-PGPUB	13:12
3 .	3	(("6372562") or ("5889293") or	USPAT;	2004/01/27
4	8575	("6303414")).PN. SOI and contact	US-PGPUB USPAT;	14:15 2004/01/27
"	6373	301 and contact	US-PGPUB	15:06
5	6884	(SOI and contact) and (doped or implanted	USPAT;	2004/01/27
		or doping or implanting)	US-PGPUB	15:06
6	5325	((SOI and contact) and (doped or	USPAT;	2004/01/27
-		implanted or doping or implanting)) and	US-PGPUB	15:06
		(gate or electrtode)		
7	5060	(((SOI and contact) and (doped or	USPAT;	2004/01/27
		implanted or doping or implanting)) and	US-PGPUB	15:07
		(gate or electrtode)) and (source or		
		drain)		2004/01/07
8	3311	((((SOI and contact) and (doped or	USPAT; US-PGPUB	2004/01/27 15:07
		implanted or doping or implanting)) and (gate or electrtode)) and (source or	03-PGP0B	13.07
		drain)) and (opening or hole or recess or		
		aperture)		
9	2533	(((((SOI and contact) and (doped or	USPAT;	2004/01/27
		implanted or doping or implanting)) and	US-PGPUB	14:18
		(gate or electrtode)) and (source or		
		drain)) and (opening or hole or recess or		
1		aperture)) and @ad<20011115		0004/01/07
10	1316		USPAT; US-PGPUB	2004/01/27
		<pre>implanted or doping or implanting)) and (gate or electrtode)) and (source or</pre>	US-PGPUB	14.21
		drain)) and (opening or hole or recess or		
		aperture)) and @ad<20011115) and (gate		
		adj (insulative or insulated or insulator		
		or insulating or dielectric))		
11	1163	SOI and contact	EPO; JPO;	2004/01/27
			DERWENT;	15:06
			IBM_TDB	2004/01/07
13	284	(SOI and contact) and (doped or implanted	EPO; JPO;	2004/01/27
		or doping or implanting)	DERWENT; IBM TDB	15:06
14	140	((SOI and contact) and (doped or	EPO; JPO;	2004/01/27
1 4	140	implanted or doping or implanting)) and	DERWENT;	15:07
		(gate or electrtode)	IBM TDB	
15	101		EPO; JPO;	2004/01/27
		implanted or doping or implanting)) and	DERWENT;	15:07
		(gate or electrtode)) and (source or	IBM_TDB]
		drain)		
16	24	((((SOI and contact) and (doped or	EPO; JPO;	2004/01/27
		implanted or doping or implanting)) and	DERWENT;	15:07
		(gate or electrtode)) and (source or drain)) and (opening or hole or recess or	IBM_TDB	
		aperture)		
	L	apercure/	L	L